

ABSTRACT

The present disclosure provides a gate drive mechanism, a process chamber, and semiconductor processing equipment. The gate drive mechanism includes a first drive apparatus, a second drive apparatus, and a connector. The connector is configured to be connected to a gate and driving-connected to the first drive apparatus and the second drive apparatus. The first drive apparatus is configured to drive the connector to move along a first direction to allow the connector to drive the gate to move along the first direction. The second drive apparatus is configured to drive the connector to move along a second direction, the second direction intersecting with the first direction, to allow the connector to drive the gate to move along the second direction relative to the first drive apparatus. By providing the second drive apparatus, the gate drive mechanism of the present disclosure can allow the gate to move horizontally. Thus, the gate can cover the liner structure to realize sealing or separate the gate from the liner. While the seal performance of the gate is ensured, the collisions and scratches between the gate and the liner structure are effectively avoided.